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1	204	345/107.ccls.	USPAT	2003/10/24
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2	209	349/89.ccls.	USPAT	2003/10/24
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3	332	359/296.ccls.	USPAT	2003/10/24
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4	528	204/450, 600.ccls.	USPAT	2003/10/24
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		427/212.s.ccis. of (427/213.s.ccis. of 427/212.ccls.) and particle\$1 WITH		
		(coat\$3 or polymer or copolymer or		
		(coat; 3 of polymer of copolymer of co-polymer)		
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		427/212.3.ccls. or (427/213.3.ccls. or		
L		427/212.ccls.)) and Tg	1	

14, and lower surfaces of these are provided with a counter electrode 6, which is made of, for example, a transparent conductive film of ITO 200 nm in thickness.

Further, a liquid crystal layer 12 (shown in FIG. 9) sandwiched between the insulating substrate 7 on the TFT 4 side and the insulating substrate 7 on the opposing side is side and the insulating substrate 7 on the opposing side is made of a fluorine-based TM liquid crystal material having, ε_p in the direction of the long axis of 7.9 (value with application of the long axis of 7.9 (value with application of the direction of the short axis of 5.3 (value with application of an effective voltage of 1.8V of 5.3 (value with application of an effective voltage of 1.8V of 5.3 (value with application of an effective voltage of 1.8V pixel pitch is 264 μm, and resolution is XGA.

Here, it is sufficient if the various materials used (other than the liquid crystal) are equivalent from the point of view of the circuit. Further, the esanning lines I, the gate electrode G, and the common lines I7 may alternatively be made of a metal of high melting point, such as aluminum or aluminum aloy which are often used in integrated circuits (ICs). The gate insulating layer 8 of the TFT 4 may alternatively have a laminated structure of silicon oxide and silicon nitride films, or of an anotized film and a silicon nitride film. Further, the contact layer 10 may be made of an amorphous silicon n⁺ layer instead of a microcrystalline silicon n⁺ layer, and the drain and source electrodes D and S may alternatively be made of a barrier metal such as Ti or Mo.

In the foregoing liquid crystal display element, TFT channel length L was not more than 6 km, and the parameters of the liquid crystal layer 12 made of a TV liquid crystal material had effective dielectric constants $\epsilon_{\rm p}$ in the direction of the long axis and $\epsilon_{\rm p}$ in the direction of the long axis and $Y=\epsilon_{\rm p}\cdot\epsilon_{\rm p}$, satisfy $Y=A\cdot X-B$ at a axis which, if $X=\epsilon_{\rm p}+\epsilon_{\rm p}$ and $Y=\epsilon_{\rm p}\cdot\epsilon_{\rm p}$, satisfy $Y=A\cdot X-B$ at a certain point in the ranges $9.5 \le X \le 15.5$, $5.43 \le A \le 5.75$, and certain point in the ranges $9.5 \le X \le 15.5$, $5.43 \le A \le 5.75$, and

As a result, it was possible to obtain a good liquid crystal display element in which flicker in the display screen was 40 greatly suppressed, and crosstalk was not noticeable to human eyes.

The embodiments and concrete examples of implementation discussed in the foregoing detailed explanation serve solely to illustrate the technical details of the present the limits of such embodiments and concrete examples, but rather may be applied in many variations, provided such variations do not depart from the spirit of the present invention or exceed the scope of the patent claims set forth provention or exceed the scope of the patent claims set forth invention or exceed the scope of the patent claims set forth present.

What is claimed is:

1. A liquid crystal display device which includes a liquid crystal material having an effective dielectric constant ϵ_p in a direction of a long axis and an effective dielectric constant of ϵ_p in a direction of a short axis which, if $X=\epsilon_p+\epsilon_p$ and $Y=\epsilon_p$ in a direction of a short axis which, if $X=\epsilon_p+\epsilon_p$ and $Y=\epsilon_p$ in a direction of a short axis which, if $X=\epsilon_p+\epsilon_p$ and $Y=\epsilon_p$ in a direction of a short axis which, if $X=\epsilon_p+\epsilon_p$ and $Y=\epsilon_p$ in a direction of a short axis which in the ranges

9.5 $\le X \le 15.5$, 5.43 $\le A \le 5.75$, and $27 \le B \le 36.2$.

2. A liquid crystal display device which includes a liquid crystal material having an effective dielectric constant ϵ_P in a direction of a long axis and an effective dielectric constant ϵ_V in a direction of a short axis which, if $X = \epsilon_P + \epsilon_V$ and $\epsilon_V = \epsilon_P = \epsilon_V = \epsilon$

10.2 $\le X \le 14.7$, 5.43 $\le A \le 5.75$, and 27 $\le B \le 36.2$.

3. A liquid crystal display device which includes a liquid 65 crystal material having an effective dielectric constant a direction of a long axis and an effective dielectric constant $\epsilon_{\mathbf{v}}$ in a direction of a short axis which, if $X = \epsilon_{\mathbf{v}} + \epsilon_{\mathbf{v}}$ and $\epsilon_{\mathbf{v}}$ in a direction of a short axis which, if $X = \epsilon_{\mathbf{v}} + \epsilon_{\mathbf{v}}$ and

As a result, it was possible to obtain a good liquid crystal display element in which flicker in the display screen was greatly suppressed, and crosstalk was not noticeable to human cyes.

Example 3

The following will explain another example of the present invention. For ease of explanation, members having the Example I above will be given the same reference symbols, and explanation thereof will be omitted here.

In the present Example, the liquid crystal layer 12 (shown in FIG. 6) sandwiched between the insulating substrate 7 on the opposing the TFT 4 side and the insulating substrate 7 on the opposing side was a fluorine-based TM liquid crystal material having, within an operating range of 2V to 5.5V, a dielectric constant $\epsilon_{\rm F}$ in the direction of the long axis of 7.3 (value with application of an effective voltage of 5.5V to the liquid crystal) and a dielectric constant $\epsilon_{\rm V}$ in the direction of the short axis of 5.5V to the liquid crystal). Further, cell thickness voltage of 2V to the liquid crystal), Further, cell thickness T_{col} was 4.5 µm, pixel pitch was 264Am, and resolution was XGA.

Other conditions were equivalent to those in Examples 1 and 2 above.

In the foregoing liquid crystal display element, TFT channel length L was not more than 6 km, and the parameters of the liquid crystal layer L2 made of a TW liquid crystal material had effective dielectric constants ϵ_p in the crystal material had effective dielectric constants ϵ_p in the direction of the long axis and ϵ_v in the direction of the short axis which, if $X=\epsilon_p+\epsilon_v$ and $Y=\epsilon_p\cdot\epsilon_v$, satisfy $Y=A\cdot X=B$ at a satisfy which, if $X=\epsilon_p+\epsilon_v$ and $X=\epsilon_p\cdot\epsilon_v$, satisfy $X=A\cdot X=B$ at a certain point in the ranges 9.5 $\le X \le 15.5$, 5.43 $\le A \le 5.75$, and $27 \le B \le 36.2$.

As a result, it was possible to obtain a good liquid crystal display element in which flicker in the display screen was greatly suppressed, and crosstalk was not noticeable to human cyes.

Example 4

The following will explain a further example of the present invention with reference to FIGS. 8 and 9. For ease shown in the drawings pertaining to Example 1 above will be given the same reference symbols, and explanation thereof will be omitted here.

As shown in FIGS. 8 and 9, TFTs 4 are provided on an insulating substrate 7. Scanning lines 1, common lines 17, and a gate electrode G have, for example, laminated structures of $134 \text{N/}\alpha$ -13/134 Nx, with the α -13 having a film thickness of 340 nm.

A gate insulating layer 8 is made of, for example, a silicon nitride film 450 nm in thickness, and an intrinsic semiconductor layer 9 is made of, for example, an amorphous silicon layer. Further, a contact layer 40 nm in thickness. Further, a pixel electrode 3 is made of, for example, an in thickness.

Signal lines 16 and drain and source electrodes D and S have, for example, laminated structures of α-Ta/IaWx and ITO films, with the α-Ta having a film thickness of 260 mm. Further, on top of the foregoing members is provided a passivation layer 11 made of, for example, silicon nitride passivation haver 11 made of, for example, silicon nitride L of 4 μm and a channel width W of 10 μm.

Further, an insulating substrate 7 on the opposite side is provided with color filter layers 1.3 and black matrix layers